



08/30/00

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Attorney Docket No.: 100988.01

Date: August 30, 2000

 JC586 U.S. PTO
 09/650690


BOX PATENT APPLICATION

Director of the U.S. Patent and Trademark Office
 Washington, D.C. 20231

 CONTINUING APPLICATION TRANSMITTAL
 RULE 1.53(b)

Sir:

Transmitted herewith for filing under 37 C.F.R. §1.53(b) is a

☐ Continuation☒ Divisional☐ Continuation-in-Part

application of prior pending Application No. 09/103,394, filed June 24, 1998,

For (Title): METHOD FOR MANUFACTURING THIN FILM MAGNETIC HEAD WITH
 IMPROVED PERFORMANCE

By (Inventors): Yoshitaka SASAKI, Atsushi IJIMA and Kazumasa FUKUDA

1. ☒ A Declaration and Power of Attorney is attached. The attached Declaration and Power of Attorney is:
 - ☒ a. A copy of the Declaration and Power of Attorney from the parent application. (Used with the same or fewer inventors and (a) a copy of the prior application or (b) a revised, reformatted or edited version of the prior application that does not contain new matter.)
 - ☐ b. A new Declaration and Power of Attorney. (Used with the same, fewer or additional inventors and (a) a copy of the prior application, (b) a revised, reformatted or edited version of the prior application that does not contain new matter, or (c) a new specification.)
2. ☒ The filing fee is calculated below:

 CLAIMS IN THE APPLICATION AFTER ENTRY OF
 ANY PRELIMINARY AMENDMENT NOTED BELOW

FOR:	NO. FILED	NO. EXTRA
BASIC FEE		
TOTAL CLAIMS	12 - 20	= ---
INDEP CLAIMS	1 - 3	= ---
<input type="checkbox"/> MULTIPLE DEPENDENT CLAIMS PRESENTED		

* If the difference is less than zero, enter "0".

SMALL ENTITY

RATE	FEE
	\$ 345
x 9 =	\$
x 39 =	\$
+130 =	\$
TOTAL	\$

OTHER THAN A SMALL ENTITY

RATE	FEE
	\$ 690
x 18	\$---
x 78	\$---
+260	\$---
TOTAL	\$690

3. ☒ Check No. 111464 in the amount of \$690 to cover the filing fee is attached. The Director is hereby authorized to charge any other fees that may be required to complete this filing, or to credit any overpayment, to Deposit Account No. 15-0461. Two duplicate copies of this sheet are attached.
4. ☐ Cancel claims _____ of the application before calculating the filing fee. At least one independent claim is retained for filing purposes.

 DEPOSIT ACCOUNT USE
 AUTHORIZATION

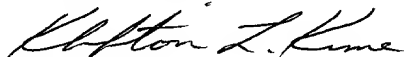
Please grant any extension
 necessary for entry;
 Charge any fee due to our
 Deposit Account No. 15-0461

5. ☒ Amend the specification by inserting before the first line the sentence:
--This is a ☐ Continuation ☒ Division ☐ Continuation-in-Part of Application No. 09/103,394 filed June 24, 1998. The entire disclosure of the prior application(s) is hereby incorporated by reference herein in its entirety.--
6. ☒ Formal drawings (Figs. 1-29) are attached.
7. ☒ Priority of foreign application(s) No. 9-317,817 filed November 19, 1997 in Japan is claimed under 35 U.S.C. § 119 and/or § 365(b).
☒ The certified copy was filed in prior Application No. 09/103,394 on September 14, 1998.
☐ A certified copy of the above foreign application(s) is filed herewith.
8. ☐ Priority of U.S. Provisional Application(s) No. _____ filed _____ is claimed under 35 U.S.C. § 119.
☐ Amend the specification by inserting before the first line the sentence:
--This nonprovisional application claims the benefit of U.S. Provisional Application(s) No. _____ filed _____--
9. ☒ The prior application is assigned of record to TDK CORPORATION recorded at Reel 9459, Frame 0956.
10. ☐ This application is filed by fewer than all the inventors named in the prior application (37 C.F.R. § 1.53(b)(1)). Delete the following inventor(s) named in the prior application:

11. ☒ A Preliminary Amendment is attached. Claims added by this Amendment are properly numbered consecutively beginning with the number next following the highest numbered claim in the application.
12. ☒ An Information Disclosure Statement is attached.
13. ☐ Small entity status:
☐ a. A small entity statement is attached.
☐ b. A small entity statement was filed in the parent application and such status is still proper and desired.
☐ c. Small entity status is no longer claimed.
14. ☐ Other: _____
15. ☒ The power of attorney in the application is to James A. Oliff, Registration No. 27,075, William P. Berridge, Registration No. 30,024, Kirk M. Hudson, Registration No. 27,562, Thomas J. Pardini, Registration No. 30,411, Edward P. Walker, Registration No. 31,450, Robert A. Miller, Registration No. 32,771, Mario A. Costantino, Registration No. 33,565, and/or Stephen J. Roe, Registration No. 34,463.
☒ a. The power appears in the attached Declaration and Power of Attorney.
☐ b. Since the power does not appear in the attached Declaration and Power of Attorney, a substitute Power of Attorney is also attached.
16. ☒ Address all future communications to:

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Respectfully submitted,



James A. Oliff
Registration No. 27,075

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	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15	16	17	18	19	20	21	22	23	24	25	26	27	28	29	30	31	32	33	34	35	36	37	38	39	40	41	42	43	44	45	46	47	48	49	50	51	52	53	54	55	56	57	58	59	60	61	62	63	64	65	66	67	68	69	70	71	72	73	74	75	76	77	78	79	80	81	82	83	84	85	86	87	88	89	90	91	92	93	94	95	96	97	98	99	100
1	1	2	3	4	5	6	7	8	9	10	11	12	13	14	15	16	17	18	19	20	21	22	23	24	25	26	27	28	29	30	31	32	33	34	35	36	37	38	39	40	41	42	43	44	45	46	47	48	49	50	51	52	53	54	55	56	57	58	59	60	61	62	63	64	65	66	67	68	69	70	71	72	73	74	75	76	77	78	79	80	81	82	83	84	85	86	87	88	89	90	91	92	93	94	95	96	97	98	99	100

In re the Application of

Application No.: Rule 53(b) Continuing Application
of U.S. Application No. 09/263,890

Docket No.: 100988.01

PRELIMINARY AMENDMENT

Sir:

IN THE TITLE:

IN THE SPECIFICATION:

Page 3, line 5, change "Cross-sectional view by which" to --a cross-sectional view in which the--;

line 7, after "are" insert --a--;

line 8, after "head" insert --, a--;

line 14, change "substance" to --substrate--;

line 17, change "3" to --3,--;

line 21, delete "as a shield gap layer 4,";

line 22, change "by the" to --as a shield gap layer 4 of a--;

line 23, change "the" (first occurrence) to --a--;

line 25, change "the" (second occurrence) to --a--;

line 28, change "and a" to --so that the--.

Page 4, line 16, change "truck" to --track--;

line 21, change "truck" to --track--;

line 22, delete "That is,".

Page 5, line 2, change "smoothed" to --smooth--;

line 20, change "as" to --by--.

Page 6, line 21, change "truck" to --track--.

Page 7, line 13, change "truck" to --track--;

line 21, change "truck" to --track--;

line 24, change "truck" to --track--;

line 28, change "truck" to --track--.

Page 8, line 14, change "The" to --the--;

line 18, change "seeing" to --as seen--;

line 20, change "truck" to --track--.

Page 9, line 8, change "effect truck" to --effective track--;

line 15, change "truck" to --track--;

line 20, change "substance" to --material--;

line 24, change "substance" to --substrate--.

Page 11, line 3, change "substance" to --substrate--.

Page 12, line 6, change "substance" to --substrate--;

line 10, change "substance" to --substrate--.

Page 14, line 7, change "substance" to --substrate--;

line 14, change ", after" to --. After--;

line 16, change ", next" to --. Next--;

line 18, change ", after making it with" to --. With--; delete ", and
then, It";

line 19, change "is shield gap layer 24 as for" to --. Thus, the--; change
"It embeds" to --is embedded--"; after "in" insert --shield gap layers 24 and--;

line 25, change ", " to --;--.

Page 15, line 2, change "light" to --write--;

line 5, change "becoming" to --, which is--;

line 7, change "weight" to --write--.

Page 16, line 13, change "is constituted" to --from changing--;

line 14, change "from changing, but as" to --. As--;

line 19, before "can" insert --the photoresist insulating layer 28'--;

line 22, change "truck" to --track--.

Page 19, line 10, change "effect truck" to --effective track--.

Page 20, line 25, change "seeing" to --as seen--.

Page 21, line 7, change "truck" to --track--;
line 8, change "truck" to --track--;
line 11, change "effect truck" to --effective track--.

Page 22, line 9, after "a" insert --satisfactory--;
line 10, delete "with enough satisfaction";
line 24, change "," to --.---;
line 27, change "seeing" to --, as seen--.

Page 23, line 1, change "truck" to --track--;
line 4, change "greatly taken" to --increased--;
line 10, change "few" to --little--.

IN THE ABSTRACT:

Line 1, change "basic substances" to --a basic substrate--;
line 2, after "25" insert --is formed and--; after "26" delete "is formed";
line 13, change "the" (second occurrence) to --a--;
line 14, after "of" (first occurrence) insert --the effective track--; delete "of the
effect truck"; change "the" (second occurrence) to --a--;
line 16, after "rear" insert --a--;
line 17, change "from" to --of--;
line 19, change "in" to --over--; after "area" insert --so that the magnetic flux
might not be saturated even when the tip portion of the upper pole is retreated from the air
bearing surface--.

IN THE CLAIMS:

Please cancel claims 1-10 without prejudice or disclaimer.

Please amend claims 16 and 21 as follows:

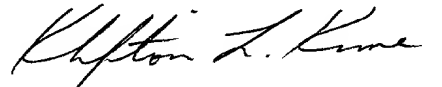
Claim 16, line 2, change "any one of claims 11 to 15" to --claim 11--.

Claim 21, line 2, change "any one of claims 18 to 20" to --claim 18--.

REMARKS

Claims 11-22 are pending. This Preliminary Amendment cancels originally pending claims 1-10 and amends claims 16 and 21 to eliminate multiple dependencies. The specification and abstract are amended to correct various informalities. The title of application is also amended. Prompt and favorable examination on the merits is respectfully requested.

Respectfully submitted,



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Registration No. 27,075

Klifton L. Kime
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JAO/KLK:amw

Date: August 30, 2000

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THIN FILM MAGNETIC HEAD AND METHOD OF MANUFACTURING THE SAME

Background of the Invention

Field of the Invention

The present invention relates to a thin film magnetic head and a method of manufacturing the same, and more particularly to a composite type thin film magnetic head constructed by stacking an inducting type writing magnetic transducing element and a magnetoresistive type reading magnetic transducing element, particularly a technique for improving a performance of a thin film writing magnetic head.

Description of the Related Art

Recently a surface recording density of a hard disc device has been improved, and it has been required to develop a thin film magnetic head having an improved performance accordingly.

The composite type thin film magnetic head has a structure for stacking a recording head intended for the writing and a reproducing head intended for the reading out, and a magnetoresistive element has been widely used in order to improve the performance of the reproducing head.

In general, as such a magnetoresistive element, the element utilizing anisotropic magnetoresistive (AMR) effect has been used so far, but there has been further developed a GMR reproducing element utilizing a giant magnetoresistive (GMR) effect having a resistance change ratio higher than the normal anisotropic magnetoresistive effect by several times. In the present specification, elements exhibiting a magnetoresistive effect such as these AMR and GMR reproducing elements are termed as a magnetoresistive reproducing element or MR reproducing element.

By using the AMR reproducing element, a very high surface recording density of several gigabits per a unit square inch² has been realized,

[illegible][illegible][illegible]

performance of the thin film magnetic recording head, it is important that the recording head and the reproducing head are formed with best balance.

Figs. 1a, 1b-9a, and 9b are cross-sectional views vertical to the air bearing surface showing the successive manufacturing steps of a conventional standard thin film magnetic head, and Cross-sectional view by which magnetic pole section is cut in parallel to the air bearing surface. Moreover, Figs. 10-12 are cross-sectional view of the entire conventional completed thin film magnetic head cross-sectional view of the magnetic pole section, and a plan view of the entire thin film magnetic head, respectively. Moreover, the thin film magnetic head of this embodiment is a composite type thin film magnetic head formed by stacking the induction type thin film writing magnetic head and the MR reproduction reading element.

First of all, as shown in Figs. 1a and 1b, an Insulation layer 2 consisting of for example alumina (Al_2O_3) is deposited on a basic substance 1 consisting of non-magnetic and electrical insulation material for example, such as AlTiC with a thickness of about 5-10 μm .

Next, as shown in Figs. 2a and 2b, a lower shield layer 3 which composes a magnetic shield protecting the MR reproduction element of the reproducing head from the influence of the external magnetic field, is formed with the thickness of 3 μm .

Afterwards, as shown in Figs. 3a and 3b, as a shield gap layer 4, after sputtering and depositing alumina by the thickness of 100-150 nm, a magnetic resistance layer 5 consisting of the material with the effect of magnetic resistance and composing the MR reproduction element is formed on the shield gap layer with the thickness of tens nano meter, thereby making high precise mask alignment.

Then, as shown in the Fig. 4, again, a shield gap layer 6 is formed and a magnetic resistance layer 5 is embedded in the shield gap layers 4 and 6.

Next, as shown in the Fig. 5, a magnetic layer 7 consisting of permalloy is formed with the film thickness of 3 μm . This magnetic layer 7 has not only a function of the upper shield layer which magnetically shields the MR reproduction element together with the above described lower shield layer 3, but also has a function of a lower magnetic layer of the thin film magnetic writing head. Herein, for convenience' sake of the explanation, this magnetic layer 7 is called as a first magnetic layer by paying attention to it a magnetic layer composing a writing magnetic head.

Then, on the first magnetic layer 7, after a light gap layer 8 consisting of non-magnetic material, for example alumina is formed with film thickness of about 200 nm, a second magnetic layer 9 consisting of material with high saturation magnetic flux density such as, for example, permalloy (Ni : 50 wt %, Fe : 50 wt %) and nitride iron (FeN) is formed with a desired shape by high precise mask alignment. Second magnetic layer 9 molded in a given shape is called a pole chip, and the width of the truck is defined as a width W.

In this case, when a dummy pattern 9' for connecting a lower pole (first magnetic layer) and an upper pole (third magnetic layer), which is formed latter, are formed simultaneously, it is possible to make an opening for through-hole after a polishing or chemistry-mechanical polishing (CMP).

In order to prevent a width of effective writing truck from being widened, that is, That is, in order to prevent a magnetic flux from being widened in the lower pole at the data writing, also a gap layer 8 in surroundings of the pole chip 9 and the lower pole 7 (first magnetic layer) are etched by an ion beam etching, such as, ion miring. Even though its state is shown in Fig. 5b, this structure is called as a trim, and this portion becomes a magnetic pole section in the first magnetic layer.

Next, as shown in Figs. 6a and 6b, after an insulating layer, for

example, alumina film 10 is formed with the thickness of about 3 μm , the whole is, for example, made smoothed by CMP.

Subsequently, after forming a photoresist layer 11 of electrical insulation to a given pattern by the mask alignment of high precision, a thin film coil 12 as the first layer consisting, for example, of copper is formed on the photoresist layer 11.

Continuously, as shown in Figs. 7a and 7b, after forming an insulating photoresist layer 13 is formed on the thin film coil 12 by the mask alignment of high accuracy again, in order to make the surface smooth, the calcining (baking) processing is given with the temperature of for example 250-300°C.

In addition, as shown in Figs. 8a and 8b, the thin film coils 14 as the second layer are formed on the smoothed surface of this photoresist layer 13. Next, after forming a photoresist layer 15 with highly accurate mask alignment on the thin film coils 14 as this second layer, in order to make the surface smooth again, the calcining (baking) processing is given with the temperature of for example 250°C.

As described above, the reason why photoresist layers 11, 13 and 15 are formed with mask alignment of high accuracy, is that throat height and MR height are defined as a reference position at the end edge of the magnetic pole section side of the photoresist layer.

Next, as shown in Figs. 9a and 9b, a third magnetic layer 16 consisting of for example permalloy is selectively formed on the second magnetic layer 9 (pole chip) and the photoresist layers 11, 13 and 15 with the thickness of 3 μm according to desired pattern.

This third magnetic layer 16 comes in contact with the first magnetic layer 7 at a rear position away from the magnetic pole section through a dummy pattern 9', thin film coil 12, 14 is extended through a closed

magnetic circuit composed by the 1st, 2nd and 3rd magnetic layers.

In addition, an overcoat layer 17 consisting of alumina deposited from the exposed surface of the third magnetic layer 16.

Finally, the side surface forming the magnetic resistance layer 5 and the gap layer 8 is ground, thereby forming an air bearing surface (ABS) 18 opposite to the magnetic record medium. Magnetic resistance layer 5 is also ground in the formation process of this air bearing surface 18, and thus, MR reproduction element 19 is obtained. In this way, the above described throat height TH and the MR height MRH are decided. Its appearance is shown in Fig. 10. In an actual thin film magnetic head, the conductor and the point of contact pad for performing electrical connection for the thin film coils 12, 14 and a MR reproduction element 19 are formed, but this is not shown.

As shown in Fig. 10, an angle θ between line segments S connecting corners of side surfaces of photoresist layers 11,13,15 for isolating the thin film coils 12,14 and an upper surface of the third magnetic layers 16 is called as an apex angle thereby becoming an important factor for deciding a performance of the thin film magnetic head together with the above described throat height TH and MR height.

Moreover, as shown in Fig. 12 by the plane, a width W of the magnetic pole section 20 between the second magnetic layer 9 and the 3rd magnetic layer 16 is made narrow, and the width of the track recorded in the magnetic record medium is defined by this width, so that it is necessary to narrow this width W as much as possible to achieve a high surface recording density. Moreover, in this Fig. 12, for the sake's of convenience of drawing, the thin film coils 12, 14 are made concentric circle.

Well, in forming conventional thin film magnetic head, especially, the problem is that after forming the coil, the coil section covered with the photoresist insulation layer and risen in the mountain shape, especially, it is a

difficulty of a fine formation of the upper pole (yoke pole) formed along the inclined part (Apex). That is, the hitherto, in case of forming the upper pole, after plating the material for the upper pole such as permalloy on the mountain shaped coil with the height of about 7-10 μm , the photoresist is spread with the thickness of 3-4 μm , after which a given pattern is formed by using the photolithography technology. Herein, If 3 μm or more is necessary as the film thickness of resist that the patterning is performed by the register strike on the mountain shaped coil, the photoresist of the about 8-10 μm thickness will be spread under the inclined portion.

On the one hand, in the upper pole formed on the write gap layer which is formed on the surface and the smooth surface of a certain mountain shaped coil section having the height difference of about such 10 μm , it is necessary to form the narrow track of the recording head near the edge in the photoresist insulation layer (11, 13 of for example Fig. 7). Therefore, it is necessary to form the pattern of the width of 1 μm with the photoresist film of thickness of 8-10 μm .

However, even if the narrow width pattern of 1 μm level is formed with a photoresist film as thick as 8-10 μm , in case of exposing the photolithography, the pattern crumble or the like due to the reflection of light is generated, and the decrease in the resolution is forced due to the thick resist, so that it is extremely difficult to form a top pole for forming the narrow track by the patterning with accuracy.

Then, as is shown in the above conventional embodiment, assuming that data is written with the pole chip capable of forming the narrow track width of the recording head, after forming this pole chip, by adopting a method of connecting the upper pole to this pole chip, in other words, by adopting a structure divided into two, that is, a pole chip for determining the track width and an upper pole for inducing magnetic flux, the above problem

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[illegible]

- [illegible]

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Moreover, other object of the present invention is to provide a thin film magnetic head in which widening of the width of the effect track and the decrease in the yield or the like were also canceled, and its manufacturing method.

98047 (9-317,817)

In a suitable embodiment of the thin film magnetic head according to the present invention, the width of second magnetic layer is widened at the region rear the pole portion.

In addition, in the present invention, the second magnetic layer consists of substance having a high saturation flux density.

In addition, in the embodiment of the thin film magnetic head according to the present invention, the insulation layer where the end edge of the magnetic pole section side becomes a reference position to the air bearing surface is provided on the above first magnetic layer, the surface of this insulation layer is covered with the gap layer consisting of the above non-magnetic material, and the above second magnetic layer is arranged along the surface opposite to the above insulation layer of this gap layer the above second magnetic layer.

In addition, the manufacturing method of the thin film magnetic

head according to the present invention comprising: step of forming a first magnetic layer having a magnetic pole section so as to support it by a basic substance, a step of forming a first insulating layer having an end edge of the magnetic pole section side as a reference position for the air bearing surface, a step of forming a gap layer consisting of non-magnetic material on the magnetic pole portion in the above first magnetic layer and the above first insulation layer, a step of forming a second magnetic layer over the magnetic pole portion in the above first magnetic layer and the rear region therefrom on the gap layer, a step of forming a thin film coil supported in the state isolated with each other by the second insulation layer above the first insulating layer, a step of forming on the above second insulation layer a third magnetic layer coming in contact with the above second magnetic layer at the region rear rather than at least the magnetic pole portion, and coming in contact with the above first magnetic layer at a rear position away from the above air bearing surface, and a step of forming an air bearing surface opposed to the magnetic record medium by grinding the above basic substance, the magnetic pole portion of the first and second magnetic layers and the gap layer placed therebetween.

In a suitable embodiment of the manufacturing method of the thin film magnetic head according to the present invention, the above second magnetic layer is formed in such a manner that the width of a magnetic layer in a rear region is gradually expanded than the magnetic pole portion.

Moreover, in a suitable embodiment of the manufacturing method of the thin film magnetic head according to the present invention, before forming the gap layer where the above first magnetic layer consists at least of non-magnetic material on the magnetic pole portion, the insulation layer where the edge on the magnetic pole portion side becomes a reference position to the air bearing surface, is formed, and in case of forming the gap layer, the

above insulation layer is covered with non-magnetic thin film which forms the gap layer.

Moreover, in the manufacturing method of the thin film magnetic head according to the present invention, a magnetoresistive reading reproducing element insulated in electrically and shielded in magnetically is arranged between the above basic substance and the first magnetic layer to construct a composite thin film magnetic head.

In case of manufacturing such a composite type thin film magnetic head, the first shield layer for performing a magnetic shielding on the above basic substance, the magnetic resistance material film is formed thereon while being embed in a fourth insulation layer, after which the above first magnetic layer also serving as the second shield layer is formed, and in the grinding step for forming the above air bearing surface, the above first shield layer is ground and the above magnetic resistance material film is ground, thereby forming a magnetoresistive reproducing element which exposes its end surface on the air bearing surface.

Brief Explanation of Drawings

Figs. 1a, 1b-9a, and 9b are cross-sectional views normal to the air bearing surface and cross-sectional views parallel to the air bearing surface in the successive manufacturing steps of a conventional standard thin film magnetic head;

Fig. 10 is a cross-sectional view normal to the air bearing surface of the conventional completed thin film magnetic head;

Fig. 11 is a parallel cross-sectional view parallel to the air bearing surface of the magnetic pole section of the conventional completed thin film magnetic head;

Fig. 12 is a plan view of the conventional completed thin film magnetic head;

Figs. 13a, 13b-8a, and 18b are parallel cross-sectional views normal to the air bearing surface showing the successive manufacturing steps in one embodiment of the manufacturing method of the thin film magnetic head according to the present invention;

Fig. 19 is a plan view showing one embodiment of the shape of the second magnetic layer;

Fig. 20 is a plan view showing other embodiments of the shape of the second magnetic layer;

Figs. 21a, 21b-24a, and 24b are cross-sectional views normal to the air bearing surface and cross-sectional views parallel to the air bearing surface showing the following steps of the same embodiment;

Fig. 25 is a plan view showing the shape of the suitable third magnetic layer to the shape of the second magnetic layer;

Fig. 26 is a cross-sectional view of the thin film magnetic head according to the completed present invention;

Fig. 27 is a plan view of the thin film magnetic head according to the completed present invention;

Fig. 28 is a diagrammatic plan view showing other embodiment of the thin film magnetic head according to the present invention, in which an extended angle of the portion rear the second magnetic layer is made 180° ; and

Fig. 29 is a graph showing the relation among the extending angle of a rear portion of the second magnetic layer, the overwrite characteristic, and the effective track width.

Figs. 13-25 show the manufacturing procedures of the thin film magnetic head according to the present invention in step order, and Fig. 26, 27 show a cross-sectional view and a plane view of the thin film magnetic head of the completed present invention, respectively. Moreover, in these figures, a

is a cross-sectional view normal to the air bearing surface, and b is a cross-sectional view by which the magnetic pole section is cut in parallel respect to the air bearing surface. This thin film magnetic head, moreover, is a composite type thin film magnetic head formed by stacking an induction type thin film reading magnetic head and the MR writing reproduction element.

First of all, as shown in Figs. 13a and 13b, an insulation layer 22 consisting of for example alumina (Al_2O_3) on basic substance 21 with the thickness of about 3-5 μm .

Next, as shown in Figs. 14a and 14b, in order to form a lower shield layer 23, permalloy is selectively formed with the thickness of about 3 μm on an alumina insulation layer 22 by the use of the photoresist film as the mask and the sputtering method.

Next, as shown in Figs. 15a and 15b, an insulating layer 24' of alumina is formed with the thickness of about 4-6 μm , after smoothing it by for example CMP, as shown in Figs. 16a and 16b, alumina is deposited with the thickness of 100-200 nm as a shield gap layer 24, next, a magnetic resistance layer 25 composing the MR reproduction element is formed with the thickness of few tens nm, after making it with the desired shape of mask alignment of high accuracy, a shield gap layer 26 is formed again, and then, It is shield gap layer 24 as for magnetic resistance layer 25 It embeds in 26.

Next, the first magnetic layer 27 is selectively formed with thickness of about 3-4 μm .

Afterwards, in order to eliminate a stepping level, after forming an alumina layer on the entire surface with 5-6 μm thickness, the surface of the first magnetic layer 27 in CMP is exposed, and the entire surface is made smooth, however, this alumina layer does not appear in the drawing.

Next, as shown in Figs. 17a and 17b, in order to decide a throat height TH and apex angle, after forming an insulation layer 28' is formed by

photoresist with the thickness of 2-3 μm , as shown in Figs. 18a and 18b, a light gap insulation layer 28 consisting of alumina is formed with 100-300 nm thickness.

Moreover, this embodiment shows that after the photoresist insulation layer 28' becoming a reference position by which the throat height TH and the apex angle are decided, is formed by the edge on the magnetic pole portion side, the weight gap insulation layer 28 is formed, but the order of forming these insulating layers may be made opposite. That is, after write gap insulation layer 28 is formed, the photoresist insulation layer 28' may be formed. However, if after the photoresist insulation layer 28' is formed, the write gap insulation layer 28 is formed, and the surface of the photoresist layer 28' is covered with the alumina insulation layer 28, there is following advantages. That is, the throat height TH is defined as a distance between the edge and the air bearing surface on the magnetic pole portion side of the photoresist insulation layer 28', in an actual manufacturing process, the position of the edge of the insulation layer 28' is not seen, so that this edge is formed at the desired position, and the air bearing surface is ground so as to obtain the desired throat height TH by using this edge as a reference position.

On the other hand, in case of forming the thin film coil, afterwards, a heat-treating about 250°C is performed, but the photoresist layer 28' composing the insulation layer is melt by this heating and thus the size of the pattern of the insulation layer is changed. Therefore, the above edge position of the photoresist insulation layer 28' is also changed, as a result, the size of the throat height TH which is the length of the magnetic pole portion in which this end is formed as a reference position, might also shift from the desired design value. Moreover, the MR height MRH defined as height of the magnetic resistance reproduction element from the air bearing surface is decided as well as the above described throat height TH depending on the

amount of polishing in case of grinding the air bearing surface, but this grinding is performed by using the edge of the pole portion side of the photoresist insulating layer 28' as a reference position, so that if the edge position of the insulating layer is changed by heat-treating, MR height MRH is also changed, and thus it is not possible to perform the grinding according to the design value. In addition, when the photoresist layers 33 and 35 constituting the insulating layer for isolating the photoresist layer 28' and the thin film coil described later, are melt, it is fear that the apex angle θ defined by the inclination angle on the side of these insulating layers changes. The apex angle θ also influences on the characteristic of the thin film magnetic head, and the characteristic thereof often becomes defective by its change. Therefore, it is important to prevent the edge in the photoresist layer 28' constituting the insulating layer is constituted by heat-treating about 250°C added in case of forming the thin film coil from changing, but as shown in Figs. 18a, and 18b, if after forming the photoresist insulating layer 28', an alumina insulating layer 28 of the write gap is formed, and the photoresist insulating layer 28' is covered with alumina insulating layer 28, the edge position of the photoresist insulating layer 28' does not change by the above described heat-treating, so that in addition to the throat height TH, can effectively control the gap from the desired design value of MR height MRH and the apex angle θ . Next, as shown in Figs. 18a and 18b, a second magnetic layer 29 (pole chip), deciding the width W of the writing truck, is selectively formed with the thickness of about 1-4 μm . Afterwards, the write gap around the pole chip is opened selectively, the pole portion is formed for example by etching the exposed first magnetic layer 27 with ion milling. Moreover, in the present invention, the pole portion means as shown in Fig. 18a by H, a region, in which the first magnetic layer 27, the write gap 28, and the second magnetic layer 29 (pole chip) between the edge surface of the

Well, in the present invention, in case of forming the above pole chip, as shown in Fig. 19, it is important to form a second magnetic layer 29 with not only pole portion 30, but also over a rear region widely. The reason thereof is that at the hitherto, in case of forming the second magnetic layer while touching the upper pole on the pole chip, the contact area of the pole chip and the upper pole is small, and the contact section touches it vertically, so that it is easy to saturate the magnetic flux in this portion, and thus, the writing characteristic of satisfying enough was not obtained; however, according to the present invention, the contact region of the pole chip and the upper pole is extended to not only the magnetic pole portion, but also a rear region therefrom, so that the fear of the saturation of such a magnetic flux can be effectively canceled, as a result, it comes to be able to obtain a satisfying enough a writing characteristic. Herein, when the contact area is secured enough, the contact region of a pole chip and an upper pole may be only as a rear region rather than that of the pole portion.

Herein, as to the shape of the pole chip in a rear region from the pole portion, a limitation is not present especially. That is, as shown in Fig. 19, it may be a shape postponed straight backward, and as shown in Fig. 20, it may be a shape which widened gradually while going backward. In short, the pole chip only has to come in contact from the pole portion in a rear region with an upper pole by an enough area.

Moreover, the extended length h of the pole chip from pole portion to the rear side is preferably about $2-5\ \mu\text{m}$ of the ring shaped insulating layer 28 which does not exceed its width, particularly, it is preferable to do as the thickness level of a top pole particularly desirable. Moreover, in Fig. 20, when the width angle of the pole chip in a rear region was assumed to be 90° (One side 45°) from the pole portion, it was showing. the width widening angle is not the one of the best only to this but 180° or less. There are not any problems. Especially, a desirable range of the angle is $40-180^\circ$. In this way, as shown in Fig. 20, when the rear end of the pole chip has widened in the shape of fan, not only the saturation of the magnetic flux is not caused as described above, but also an accurate pattern edge according to photolithography can be controlled by enlarging the rear end, so that a more accurate control becomes possible from the throat height's TH. Moreover, in case of forming the pole chip 29 as described above, if a dummy pattern 29' for connecting a lower pole (the first magnetic layer) and an upper pole (the third magnetic layer) at the same time, an opening of through-hole becomes easy after CMP. As described above, after forming the second magnetic layer 29, as shown in Figs. 21a and 21b, After forming for example alumina film 31 as the insulation layer is formed with the thickness of about $3\ \mu\text{m}$, the whole is smoothed by, for example, CMP. As shown in Figs. 22a and 22n, then, after forming the thin film coils 32 of the first layer consisting of for example copper on this insulation layer 31, insulative photoresist layer 33 is formed with the mask alignment of high accuracy. Subsequent, the whole is baked by the temperature of for example about 250°C to make the surface smooth. Next, as shown in Fig. 23a and 23b, after forming thin film coils 34 of the second layer and then after forming photoresist layer 35 with highly accurate mask alignment on this thin film coil 34, it bakes at for example 250°C to make the surface smooth again. Next, as shown in Figs. 24a and

24b, the third magnetic layer 36 (upper pole) consisting of for example permalloy is selectively formed with thickness of $3\ \mu\text{m}$ on the second magnetic layer 29 (pole chip), the photoresist layer 33 and 35 according to the desired pattern. In case of forming this third magnetic layer 36, as shown in Fig. 24a, it is suitable for its tip portion to form so as to retreat only distance L from the air bearing surface. The distance L is almost equal to the throat height TH. Composing in such a way, as described above, if a positional relation between the pole chip and the upper pole is shifted greatly to one side, seeing from the air bearing surface, data writing is caused even in the upper pole, a disadvantage of widening the width of the effect track is caused. However, there is an advantage that such a disadvantage comes might not generate if making the tip portion of the third magnetic layer is retreated from the air bearing surface. Moreover, hitherto, though the saturation of the magnetic flux is forced since the contact area of the pole chip and the upper pole decreases when the tip portion of the upper pole is located from the air bearing surface backward, however, in the present invention, since the contact area of both is secured enough in a rear region from the magnetic pole portion, so that the magnetic flux might not be saturated even if the tip portion of the upper pole is made retreated from the air bearing surface. Moreover, in case of forming the third magnetic layer 36, as shown in Fig. 20, it is preferable to make the shape along the shape of the second magnetic layer 29. In addition, as shown in Fig. 25, when the width angle of the second magnetic layer 29 is $30-60^\circ$ and somewhat small, First, the third magnetic layer 36 is formed with a width widening angle : $30-60^\circ$ so as to along the shape of the second magnetic layer, and then is formed with becoming a desired width angle. Thus, when the width of the third magnetic layer 36 is made wide as the magnetic layer is located away from the air bearing surface, and the third magnetic layer covers the second magnetic layer 29, even if a positioning error is caused between the

pole chip 29 and upper pole 36, the change of contact area is few as a whole, so that the saturation of the magnetic flux does not generate. Moreover, this third magnetic layer 36 comes in contact with the first magnetic layer 27 at a rear position away from the magnetic pole portion through the dummy pattern 29', it is thin film coil 32 as for the closed magnetic path constituted with the first and the second and the third magnetic layer. It is structure which passes 34 and comes off.

Next, as shown in Figs. 26a and 26b, an overcoat layer 37 consisting of alumina or the like is deposited on the exposed surface of the third magnetic layer 36. Finally, the air bearing surface 38 opposed to the magnetic record medium is formed by grinding the side surface where the magnetic resistance layer 25 and the gap layer 28 are formed. In this case, the edge on the magnetic pole portion side of the photoresist insulation layer 28' is defined as a reference position to the air bearing surface, so that the throat height TH, the MR height MRH, and the apex angle θ can be decided accurately as a desired design value. The present invention is not limited to the above embodiment and various changes and modifications may be performed. In the above described embodiment, for example, the thin film magnetic head is constructed as a composite type thin film magnetic head which is formed by stacking an induction type writing magnetic head and the reading magnetic head comprising an MR reproduction element, but this can also be constructed as induction type writing magnetic head.

Moreover, in the above embodiment, the width of rear portion of the second magnetic layer and the tip portion of the third magnetic layer which is overlapped thereto is widened gradually seeing from the air bearing surface, but as shown in Fig. 28, the connection portion of the magnetic pole portion of the second magnetic layer 29 and the rear portion may be made a right-angle. In this case, the widening angle of rear portion of the second magnetic layer

29 may be 180° . Moreover, the shape of portion of the 3rd magnetic layer 36 overlapped to the rear portion of this second magnetic layer 29 is also registered to the shape of the rear portion with a certain width. Fig. 29 shows the change in the overwrite characteristic (curve A) obtained when the widening angle α of the rear portion of the second magnetic layer 29 is changed over a range of $0-270^\circ$ and shows the change in width of the effective track width (curve B). That is, the overwrite characteristic is shown to a left vertical axis by the dB unit, and the normalized effective track width is plotted on the right horizontal axis by arbitrary unit. In general, it is demanded to make the overwrite characteristic to be -30 dB or less, and the width of the effect track is allowed to the value to be originally obtained with extension up to 10% or less. Therefore, it is understood that the widening angle α of a rear part of the second magnetic layer 29 is $40-180^\circ$ from curves A and B. In the present invention, as a material for the second magnetic layer, that is, the pole chip, in addition to the above permalloy (Ni : 50 wt%, Fe : 50 wt%) and nitride iron (FeN), the materials of the high saturation magnetic flux density such as Fe-Cr-Zr system amorphous alloys and the Fe-C system amorphous alloys are advantageously adopted. Moreover, it is all right in any way to use these materials with two kinds or more. Moreover, as a material for the first and the third magnetic layers, in addition to the above permalloy (Ni : 80 wt%, Fe : 20 wt%), well-known various high saturation magnetic flux density materials can be suitably used.

In addition, as a material for the write gap layer, Oxide such as Al_2O_3 , SiO_2 or the like, Nitride such as AlN, BN, SiN or the like, furthermore, electrically conductive and non magnetic substance such as Au, Cu, NiP or the like are used effectively.

Moreover, in the above example shown in the figure, it is explained chiefly described the case that the insulating layer, in which edge on the pole

portion side became a reference position to the air bearing surface, is formed with the photoresist layer, but this insulating layer may be formed with the alumina layer, the silicon oxidation layer, and the silicon nitride layer, or the like.

According to the present invention, the second magnetic layer (pole chip) and the third magnetic layer (upper pole) have been touched at not only the pole portion but also it in a wide rear region therefrom, so that it is possible to reach the writing pole region effectively without saturating magnetism generated in the coil on the way, and thus a writing characteristic can be obtained with enough satisfaction.

Moreover, according to the present invention, the insulating layer in which the edge on the pole portion side becomes a reference position to the air bearing surface is provided on the first magnetic layer, and if this insulating layer is covered with the write gap alumina layer, the insulating layer does not melt by heat-treating added at the time of forming the thin film coil, so that the throat height TH and the MR height MRH and furthermore, the apex angle θ can be formed according to a desired design value.

According to the present invention, the desired relation is always obtained between the MR height MRH and the throat height TH, so that the balance of the record head and the reproduction head can be kept in the best condition, and as a result, a composite type thin film magnetic head can be obtained with high performance.

In addition, according to the present invention, the tip portion of the third magnetic layer is made retreated from the air bearing surface, The contact portion of the third magnetic layer and the second magnetic layer is prevented from being exposed to the air bearing surface, so that even if seeing from the air bearing surface, mis-registration is caused in the position of a pole chip and an upper pole, the writing is performed by the upper pole,

Moreover, further according to the invention, the contact area of an upper pole and the pole chip can be greatly taken, by widening the rear end of the second magnetic layer in the shape of fan, so that magnetic flux can be effectively prevented from being saturated in this portion.

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What is claimed is:

1. A thin film magnetic head comprising: a first magnetic layer having a pole portion opposite to a magnetic record medium, a second magnetic layer opposite to the magnetic record medium and having a pole portion with a width defining a width of a record track, for constructing an air bearing surface together with an end face of the pole portion and an end face of the pole portion of the first magnetic layer, a third magnetic layer contacted to the second magnetic layer at the side opposite to the first magnetic layer and magnetically coupled to the first magnetic layer at a rear position separated from the air bearing surface, a gap layer consisting of non-magnetic substance inserted between the pole portion of the first magnetic layer and the pole portion of the second magnetic layer, a thin film coil having a portion supported between the first magnetic layer and the second and third magnetic layers in the state isolated by an insulating layer, and a base substance for supporting the first, second and third magnetic layers, the gap layer, the insulating layer and the thin film coil, characterized in that the second magnetic layer is extended to the region after than the pole portion of the first magnetic layer along a part of the face at the side opposite to the first magnetic layer, of the insulating layer supported in the state isolating the thin film coil, thereby touching the second magnetic layer to the third magnetic layer at the extended region.

2. A thin film magnetic head as claimed in claim 1, wherein the width of second magnetic layer is widened at the region rear the pole portion.

3. A thin film magnetic head as claimed in claim 2, wherein the widened angle of the second magnetic layer at the region rear than the pole portion is $40\sim 180^{\circ}$.

4. A thin film magnetic head as claimed in claim 1, wherein the length h of the second magnetic layer, of the part rear from the pole portion is

5. A thin film magnetic head as claimed in claim 1, wherein the second magnetic layer consists of substance having a high saturation flux density.

7. A thin film magnetic head as claimed in claim 6, wherein the distance backed up from the air bearing surface is made substantially equal to a throat height.

9. A thin film magnetic head as claimed in claim 1, wherein the pole portion of the first magnetic layer is a trim structure.

11. A method of manufacturing a thin film magnetic head comprising:
step of forming a first magnetic layer having a magnetic pole section so as to
support it by a basic substance, a step of forming a first insulating layer having

an end edge of the magnetic pole section side as a reference position for the air bearing surface, a step of forming a gap layer consisting of non-magnetic material on the magnetic pole portion in the above first magnetic layer and the above first insulation layer, a step of forming a second magnetic layer over the magnetic pole portion in the above first magnetic layer and the rear region therefrom on the gap layer, a step of forming a thin film coil supported in the state isolated with each other by the second insulation layer above the first insulating layer, a step of forming on the above second insulation layer a third magnetic layer coming in contact with the above second magnetic layer at the region rear rather than at least the magnetic pole portion, and coming in contact with the above first magnetic layer at a rear position away from the above air bearing surface, and a step of forming an air bearing surface opposed to the magnetic record medium by grinding the above basic substance, the magnetic pole portion of the first and second magnetic layers and the gap layer placed therebetween.

12. A method of manufacturing a thin film magnetic head as claimed in claim 11, wherein in case of forming the above second magnetic layer on the above gap layer, the width of a magnetic layer in a rear region is gradually expanded than the magnetic pole portion.

13. A method of manufacturing a thin film magnetic head as claimed in claim 11, wherein after forming the above second magnetic layer, the third insulation layer is formed to cover this second magnetic layer and the above gap layer, the surface of a rear region than the magnetic pole portion in the above second magnetic layer is exposed by grinding this third insulation layer, thereby forming a plane surface together with the third insulation layer, and the above thin film coil is formed on this plane surface.

14. A method of manufacturing a thin film magnetic head as claimed in claim 13, wherein the grinding process in the above third insulation layer is

15. A method of manufacturing a thin film magnetic head as claimed in claim 11, wherein after forming the above second magnetic layer, the above first magnetic layer is removed over a part of its film thickness to form a trim structure, by performing an etching treatment with the use of its magnetic pole portion as a mask.

17. A method of manufacturing a thin film magnetic head as claimed in claim 16, wherein the first shield layer for performing a magnetic shielding on the above basic substance, the magnetic resistance material film is formed thereon while being embed in a fourth insulation layer, after which the above first magnetic layer also serving as the second shield layer is formed, and in the grinding step for forming the above air bearing surface, the above first shield layer is ground and the above magnetic resistance material film is ground, thereby forming a magnetoresistive reproducing element which exposes its end surface on the air bearing surface.

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insulating layer, a step of forming a thin film coil in the state isolated with each other by the second insulation layer above the first insulating layer, a step of forming on the above second insulation layer a third magnetic layer coming in contact with the above second magnetic layer at the region rear rather than at least the magnetic pole portion, and coming in contact with the above first magnetic layer at a rear position away from the above air bearing surface, a step of forming an air bearing surface opposed to the magnetic record medium by grinding the above basic substance, the magnetic pole portion of the first and second magnetic layers and the gap layer placed therebetween.

19. A method of manufacturing a thin film magnetic head as claimed in claim 18, wherein in case of forming the above second magnetic layer on the above gap layer, the width of a magnetic layer in a rear region is gradually expanded than the magnetic pole portion.

20. A method of manufacturing a thin film magnetic head as claimed in claim 18, wherein after forming the above second magnetic layer, the gap layer around the above magnetic pole portion is removed over a part of its film thickness to form a trim structure, by performing an etching treatment with the use of its magnetic pole portion as a mask.

21. A method of manufacturing a thin film magnetic head as claimed in any one of claims 18 to 20, wherein a magnetoresistive reading reproducing element insulated in electrically and shielded in magnetically is arranged between the above basic substance and the first magnetic layer to construct a composite thin film magnetic head.

22. A method of manufacturing a thin film magnetic head as claimed in claim 21, wherein the first shield layer for performing a magnetic shielding on the above basic substance, the magnetic resistance material film is formed thereon while being embed in a fourth insulation layer, after which the above first magnetic layer also serving as the second shield layer is formed, and in

Cognitive Function		Mood		Quality of Life		Social Function		Health Status	
Pre-Intervention	Post-Intervention	Pre-Intervention	Post-Intervention	Pre-Intervention	Post-Intervention	Pre-Intervention	Post-Intervention	Pre-Intervention	Post-Intervention
10.5	11.2	1.2	1.5	2.1	2.8	3.4	3.9	4.5	5.1
11.2	12.1	1.5	1.8	2.8	3.5	3.9	4.4	5.2	5.8
12.1	13.0	1.8	2.1	3.5	4.2	4.4	4.9	5.6	6.2
13.0	14.0	2.1	2.4	4.2	5.0	4.9	5.4	6.2	6.8
14.0	15.0	2.4	2.7	5.0	5.8	5.4	5.9	6.8	7.4
15.0	16.0	2.7	3.0	5.8	6.6	5.9	6.4	7.4	8.0
16.0	17.0	3.0	3.3	6.6	7.4	6.4	6.9	8.0	8.6
17.0	18.0	3.3	3.6	7.4	8.2	6.9	7.4	8.6	9.2
18.0	19.0	3.6	3.9	8.2	9.0	7.4	7.9	9.2	9.8
19.0	20.0	3.9	4.2	9.0	9.8	7.9	8.4	9.8	10.4
20.0	21.0	4.2	4.5	9.8	10.6	8.4	8.9	10.4	11.0
21.0	22.0	4.5	4.8	10.6	11.4	8.9	9.4	11.0	11.6
22.0	23.0	4.8	5.1	11.4	12.2	9.4	9.9	11.6	12.2
23.0	24.0	5.1	5.4	12.2	13.0	9.9	10.4	12.2	12.8
24.0	25.0	5.4	5.7	13.0	13.8	10.4	10.9	12.8	13.4
25.0	26.0	5.7	6.0	13.8	14.6	10.9	11.4	13.4	14.0
26.0	27.0	6.0	6.3	14.6	15.4	11.4	11.9	14.0	14.6
27.0	28.0	6.3	6.6	15.4	16.2	11.9	12.4	14.6	15.2
28.0	29.0	6.6	6.9	16.2	17.0	12.4	12.9	15.2	15.8
29.0	30.0	6.9	7.2	17.0	17.8	12.9	13.4	15.8	16.4
30.0	31.0	7.2	7.5	17.8	18.6	13.4	13.9	16.4	17.0
31.0	32.0	7.5	7.8	18.6	19.4	13.9	14.4	17.0	17.6
32.0	33.0	7.8	8.1	19.4	20.2	14.4	14.9	17.6	18.2
33.0	34.0	8.1	8.4	20.2	21.0	14.9	15.4	18.2	18.8
34.0	35.0	8.4	8.7	21.0	21.8	15.4	15.9	18.8	19.4
35.0	36.0	8.7	9.0	21.8	22.6	15.9	16.4	19.4	20.0
36.0	37.0	9.0	9.3	22.6	23.4	16.4	16.9	20.0	20.6
37.0	38.0	9.3	9.6	23.4	24.2	16.9	17.4	20.6	21.2
38.0	39.0	9.6	9.9	24.2	25.0	17.4	17.9	21.2	21.8
39.0	40.0	9.9	10.2	25.0	25.8	17.9	18.4	21.8	22.4
40.0	41.0	10.2	10.5	25.8	26.6	18.4	18.9	22.4	23.0
41.0	42.0	10.5	10.8	26.6	27.4	18.9	19.4	23.0	23.6
42.0	43.0	10.8	11.1	27.4	28.2	19.4	19.9	23.6	24.2
43.0	44.0	11.1	11.4	28.2	29.0	19.9	20.4	24.2	24.8
44.0	45.0	11.4	11.7	29.0	29.8	20.4	20.9	24.8	25.4
45.0	46.0	11.7	12.0	29.8	30.6	20.9	21.4	25.4	26.0
46.0	47.0	12.0	12.3	30.6	31.4	21.4	21.9	26.0	26.6
47.0	48.0	12.3	12.6	31.4	32.2	21.9	2		

Abstract:

After forming the first shield layer 23 on basic substances 21 and 22, a GMR film 25 embedded in the shield gap layers 24 and 26 is formed, in addition, a first insulation layer 28' where the edge defines a reference position of a throat height zero is formed on a first magnetic layer 27, a gap layer 28 is formed on a magnetic pole portion of the first magnetic layer 27 and the first insulation layer, then a second magnetic layer 29 extended above the first insulation layer 38' from the upper side of the magnetic pole portion of the first magnetic layer 27 is formed, after smoothing its surface by the second insulation layer 31, thin film coils 32 and 34 are formed on this second insulation layer, and the third magnetic layer 36 is formed on the insulation layers 33 and 35 where the magnetic pole portion and the thin film coil of the second above magnetic layer are isolated. In order to cancel the saturation of the magnetic flux in the magnetic pole portion effectively, and to prevent the widening of width of the effect truck and the decrease in the yield, the third above magnetic layer is made retreated from the air bearing surface, and is connected to rear region from the magnetic pole portion of the second magnetic layer. A rear region from the magnetic pole portion of the second magnetic layer 29 is made in the shape of fan and connected to the third magnetic layer 36 in enough area.

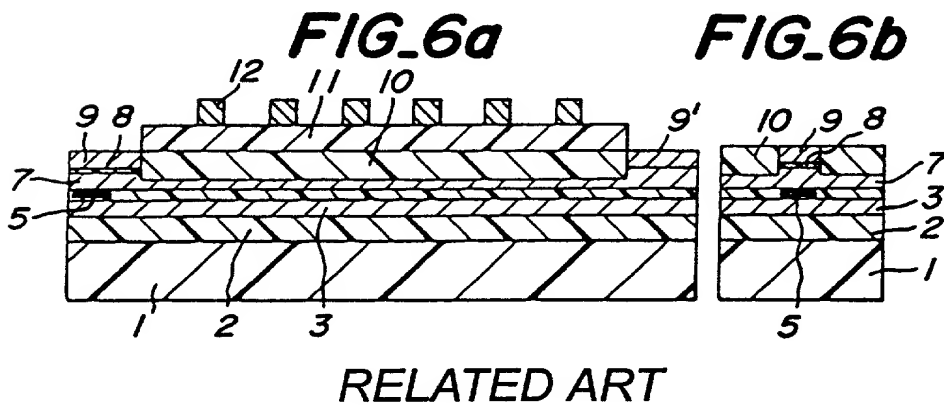
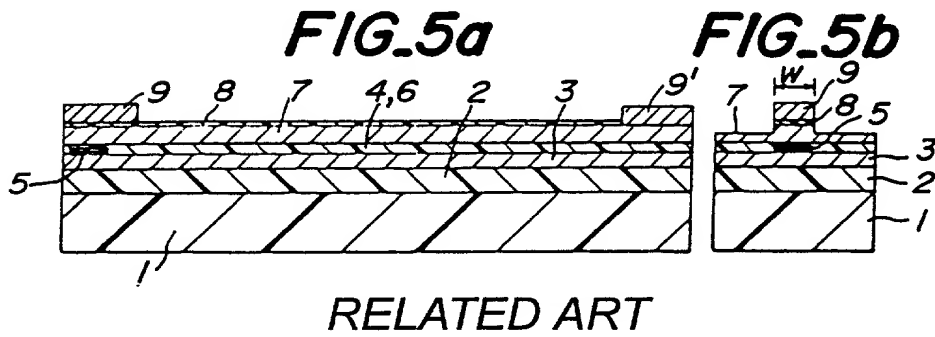
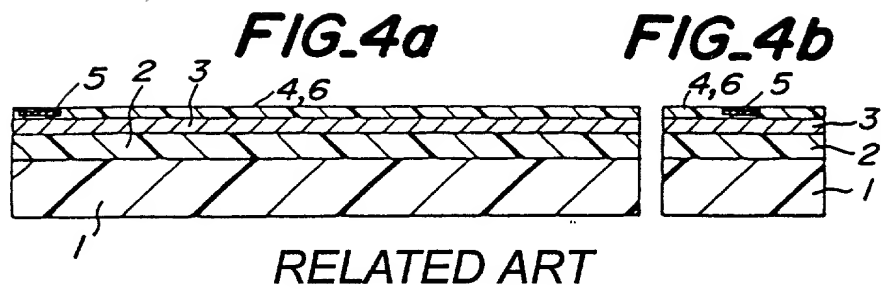


FIG. 7a

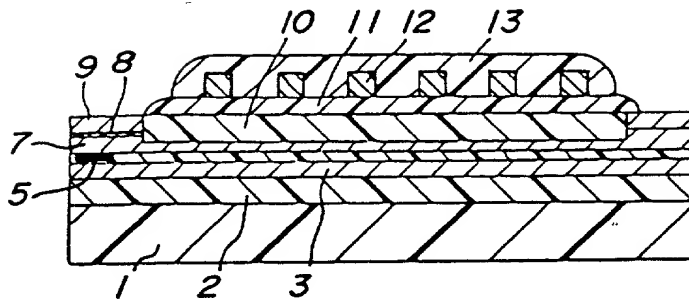
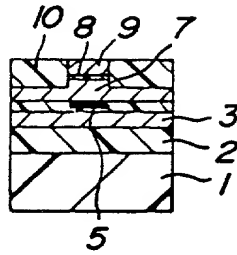


FIG. 7b



RELATED ART

FIG. 8a

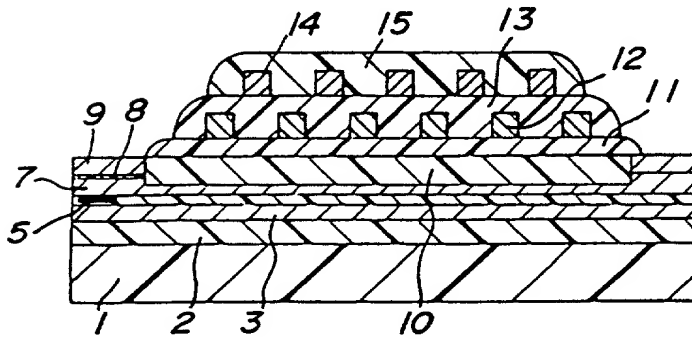
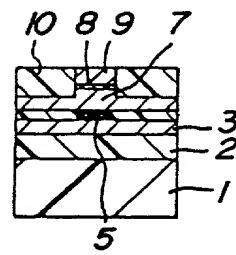


FIG. 8b



RELATED ART

FIG. 9a

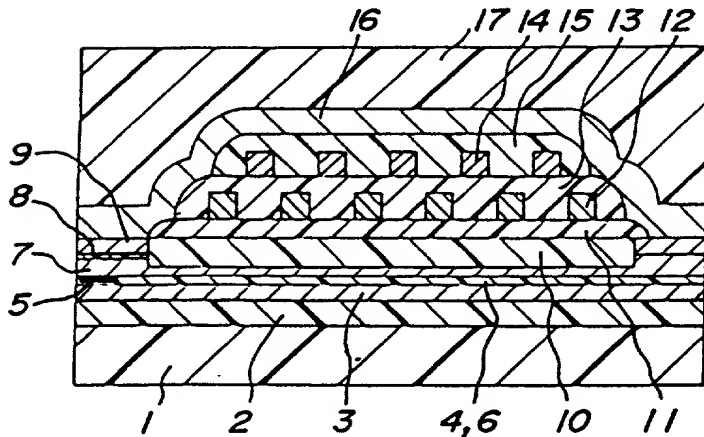
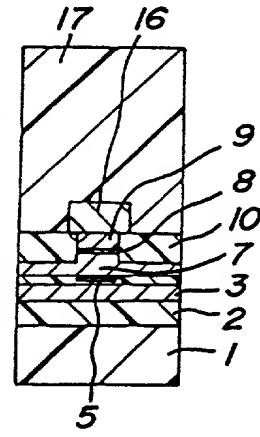


FIG. 9b



RELATED ART

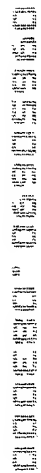
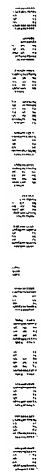
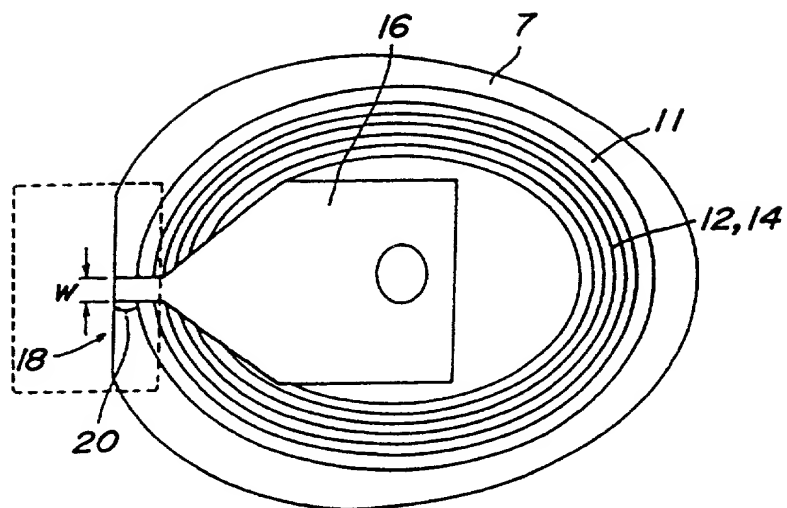
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Table 1. Demographic characteristics of the study population	
Age (years)	65.8 ± 1.2
Gender (male/female)	10/10
Education (years)	12.5 ± 0.5
Occupation (white/blue)	10/10
Marital status (married/divorced/widowed)	10/10/0
Smoking status (smoker/nonsmoker)	10/10
Alcohol consumption (yes/no)	10/10
Comorbidities (hypertension/diabetes/cholesterol)	10/10/10
Medication (antihypertensive/antidiabetic/anticholesterol)	10/10/10
Family history (hypertension/diabetes/cholesterol)	10/10/10
Physical activity (yes/no)	10/10
Stress level (low/moderate/high)	10/10/10
Social support (yes/no)	10/10
Health status (good/fair/poor)	10/10/10
Quality of life (yes/no)	10/10
Life satisfaction (yes/no)	10/10
Overall health (yes/no)	10/10

[illegible]

FIG. 12



RELATED ART

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FIG.13a

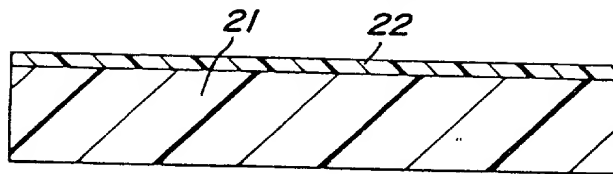


FIG.13b

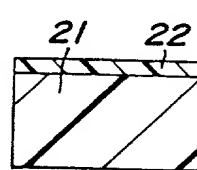


FIG.14a

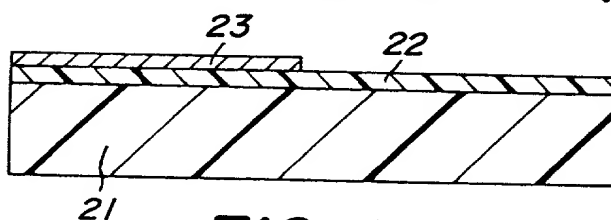


FIG.14b

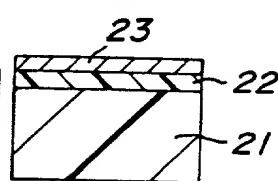


FIG.15a

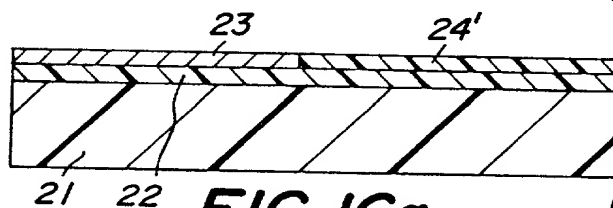


FIG.15b

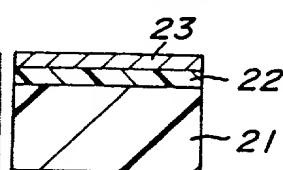


FIG.16a

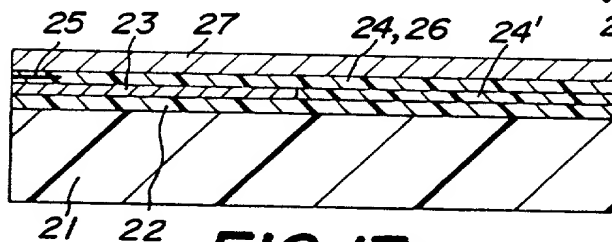


FIG.16b

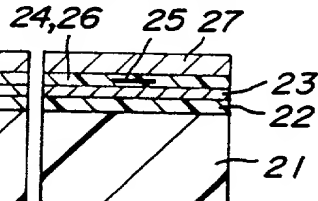


FIG.17a

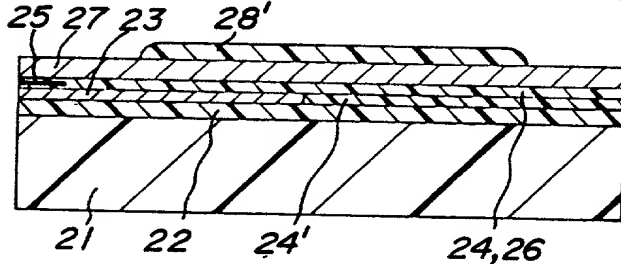


FIG.17b

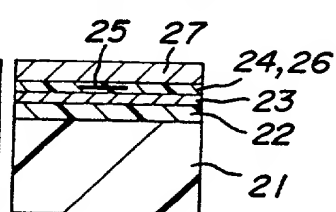


FIG. 18a

FIG. 18b

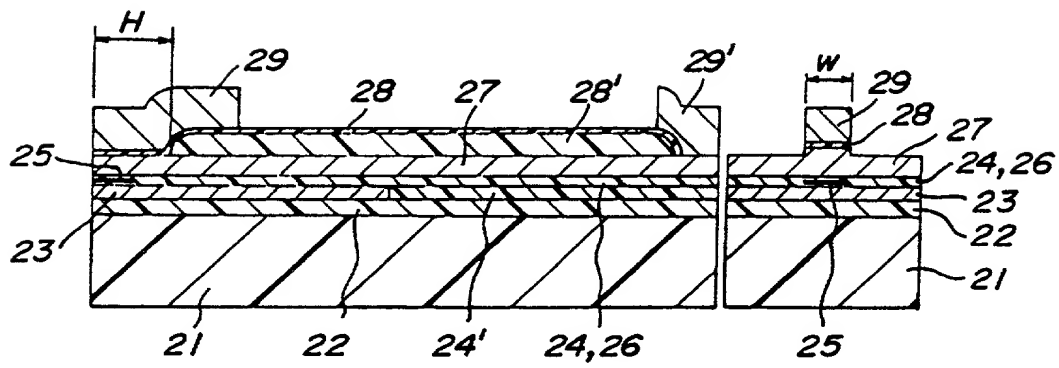


FIG. 21a

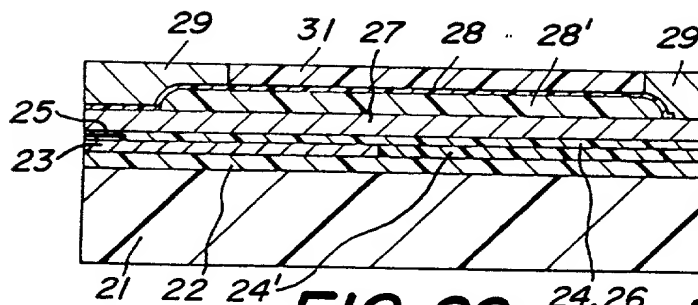


FIG. 21b

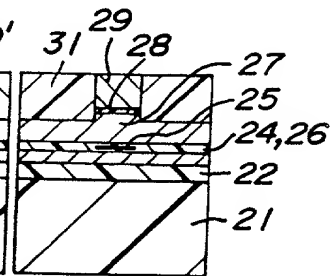


FIG. 22a

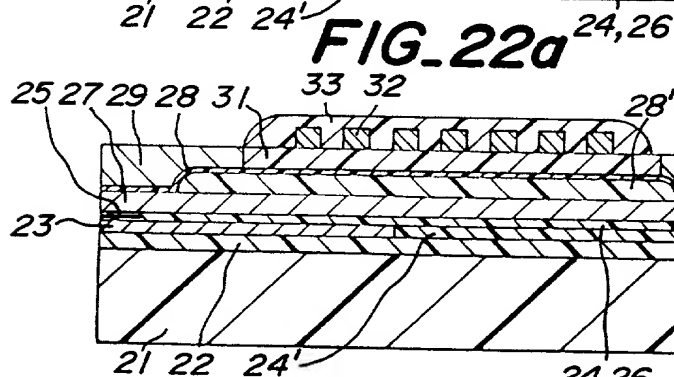


FIG. 22b

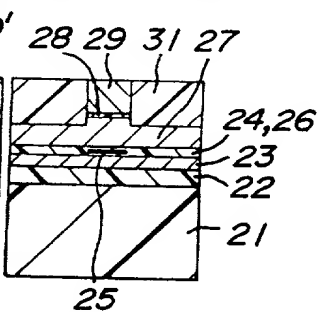


FIG. 23a'

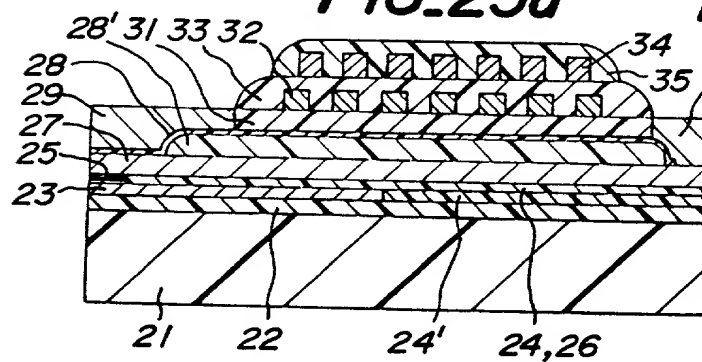


FIG. 23b

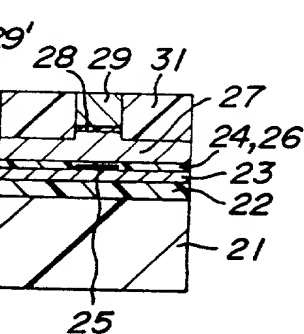


FIG. 24a

FIG. 24b

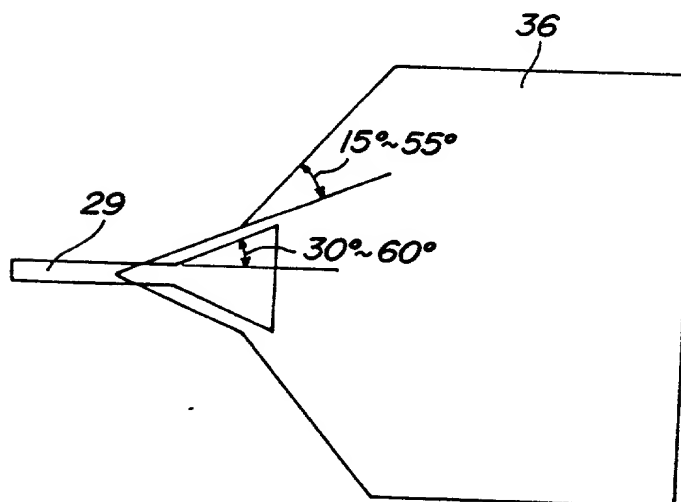
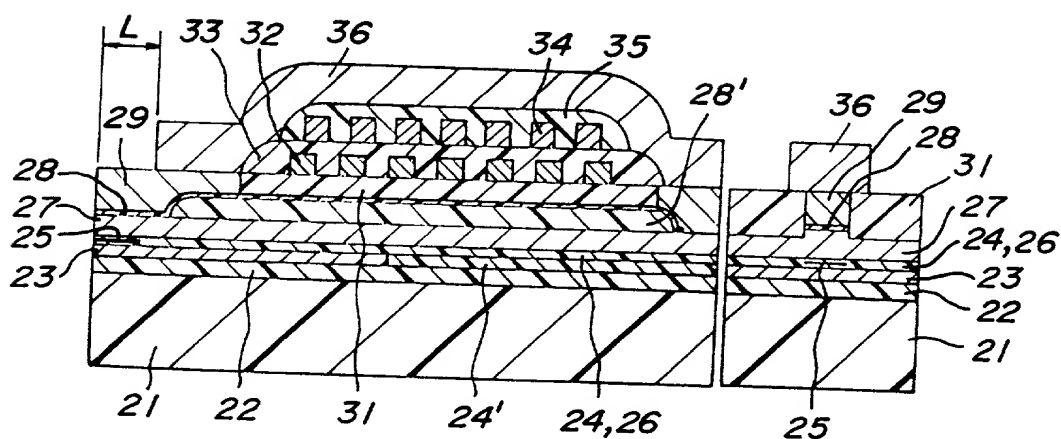


FIG. 26a **FIG. 26b**

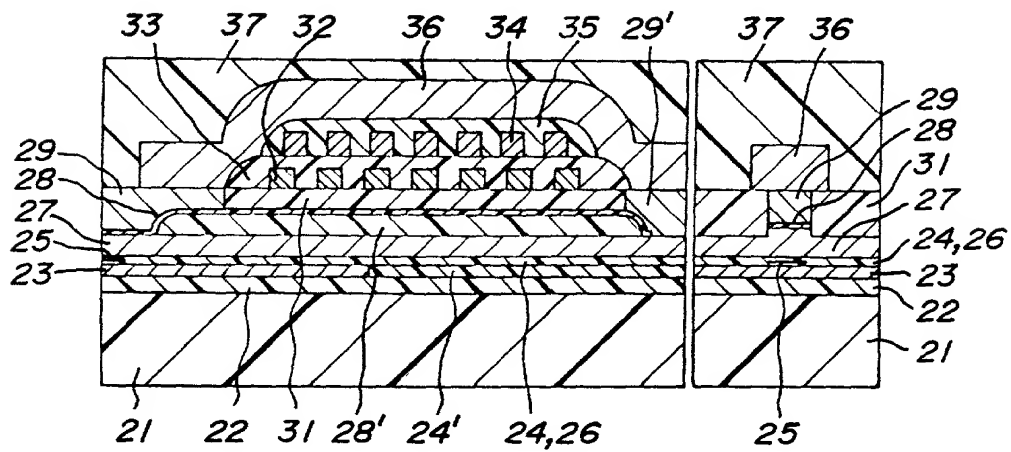
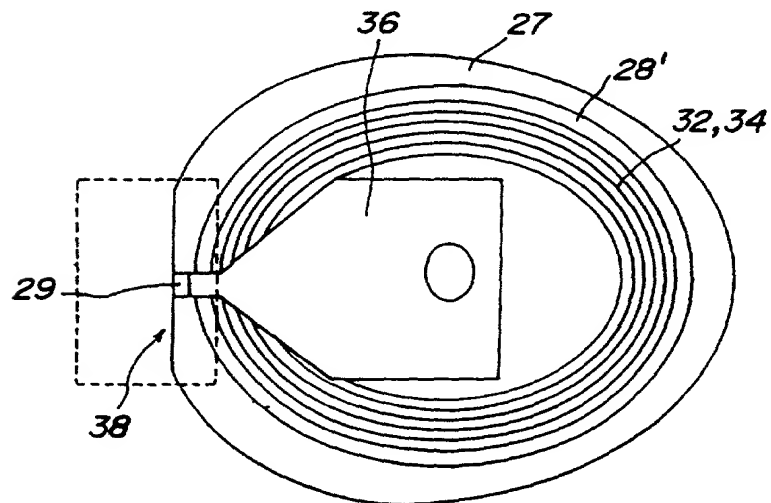


FIG. 27



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FIG. 28

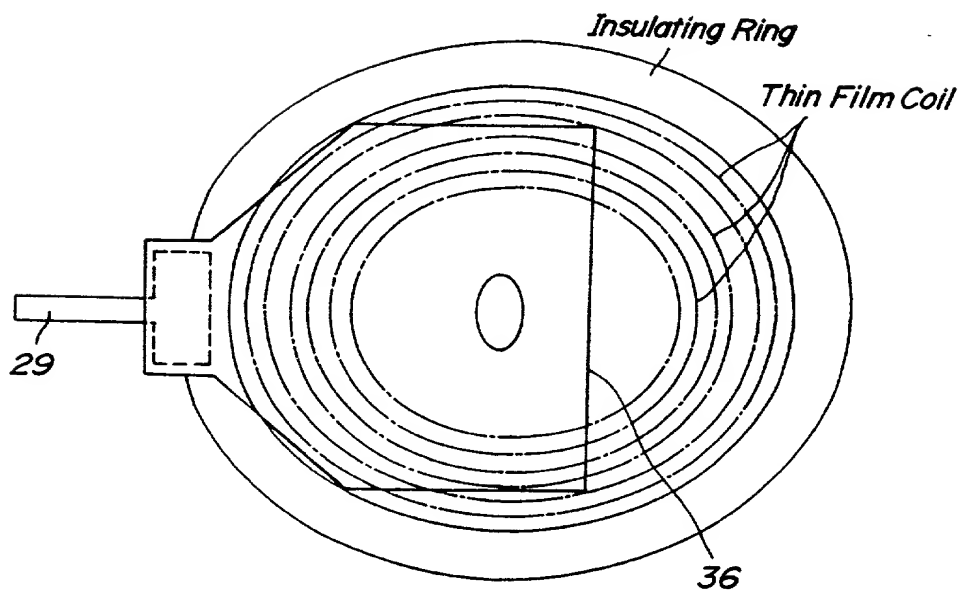
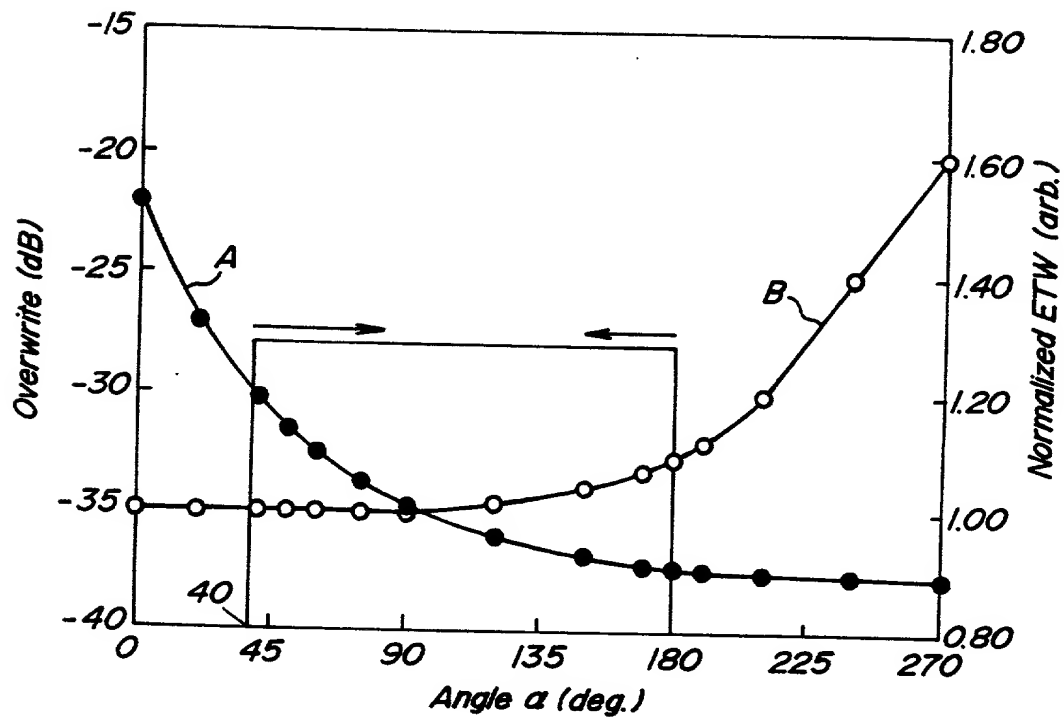


FIG. 29



(98047)

As a below named inventor, I hereby declare that:

my residence, post office address and citizenship are as stated below under
ne;

on the invention entitled:

FILM MAGNETIC HEAD AND METHOD OF MANUFACTURING THE SAME

1

one

*a. ☐ attached hereto.

b. ☒ filed on June 24, 1998 as Application Serial No. 09/103,394 .

I have reviewed and understand the contents of the above-identified application, including the claims, as amended by any amendment referred to above.

I acknowledge the duty to disclose to the Office all information known to me material to patentability as defined in Title 37, Code of Federal Regulations

Under Title 35, U.S. Code §119, the priority benefits of the following application(s) filed within one year prior to this application are hereby claimed:

James A. Oliff, Reg. No. 27,075; William P. Berridge, Reg. No. 30,024; Kirk M. Hudson, Reg. No. 27,562; Thomas J. Pardini, Reg. No. 30,411; and Edward P. Walker, Reg. No. 31,450.

CORRESPONDENCE IN CONNECTION WITH THIS APPLICATION SHOULD BE SENT TO OLIFF &
 OGE, P.O. BOX 19928, ALEXANDRIA, VIRGINIA 22320, TELEPHONE (703) 836-6400.

I hereby declare that I have reviewed and understand the contents of this application, and that all statements made herein of my own knowledge are true and correct, and all statements made on information and belief are believed to be true; and I declare that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code and that such willful false statements may jeopardize the validity of the application or any patent issued thereon.

Written Full Name
Last Name or First Inventor Yoshitaka SASAKI
Given Name / / Middle Initial / / Family Name

Director's Signature Yashitaka Sasabe

of Signature September 7, 1998

City	Yokohama City, Kanagawa Pref., Japan		
State or Province			
Country			

enship _____ Japanese

Post Office Address 1-4-28, Nakatahigashi, Izumi-Ku, Yokohama City,
(Insert complete mailing Kanagawa Pref., Japan
address, including country)

Box a. is checked, this form may be executed only when attached to the application (including claims) at the end thereof.

To Inventor: Please sign name on line 2 exactly as it appears in line 1 and the actual date of signing on line 3.

IF THERE IS MORE THAN ONE INVENTOR USE PAGE 2 AND PLACE AN "X" HERE ☒

Variable	Mean	Standard Deviation	Minimum	Maximum
Age	34.5	10.2	22	55
Gender	0.5	0.5	0	1
Marital Status	0.6	0.5	0	1
Education	12.5	1.5	10	15
Income	3500	1500	1000	7000
Health	0.8	0.2	0	1
Smoking	0.3	0.5	0	1
Alcohol	0.2	0.4	0	1
Exercise	0.4	0.5	0	1
Stress	0.6	0.5	0	1
Depression	0.1	0.3	0	1
Loneliness	0.3	0.4	0	1
Life Satisfaction	0.7	0.2	0	1
Quality of Life	0.8	0.1	0	1
Overall Health	0.9	0.1	0	1

1	Type-written Full Name of Joint Inventor			
	Given Name	Middle Initial	Family Name	
2	Inventor's Signature			
3	Date of Signature			
	Residence			
	City	State or Province		Country
	Citizenship			
	Post Office Address			
	(Insert complete mailing address, including country)			

This form may be executed only when attached to the first page of the Declaration and Power of Attorney of the application to which it pertains.